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surface NEAR5 (roughen\$3 or textur\$5 or treatment) and electron adj beam Us-pepuB; EPO; JPO; BERWENT;						DERWENT;	
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(250/\$.ccls.) and (surface WITH (roughen\$3 or textur\$5 t)) and electron adj USPAT; BM_TDB USPQUB; EPO; JPO; DeRWENT; BM_TDB USPQUB; EPO; JPO; DeRWENT; BM_TDB USPQUB; EPO; JPO; Deam) and (stress or aneal) ((250/\$.ccls.) and (surface near (roughen\$3 or textur\$5 t)) and electron adj USPQUB; EPO; JPO; DERWENT; BM_TDB USPQUB; EPO; JPO; DERWENT; DE					***	EPO: 190:	
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